IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kenneth C. Johnson et al.

Application No.: NEW

Filed: HEREWITH

For: DATABASE INTERPOLATION METHOD

FOR OPTICAL MEASUREMENT OF DIFFRACTIVE MICROSTRUCTURES

Group Art Unit: Unknown

Examiner: Unknown

INFORMATION DISCLOSURE STATEMENT

121 Spear Street, Suite 290 San Francisco, CA 94105

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M/S PATENT APPLICATION Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

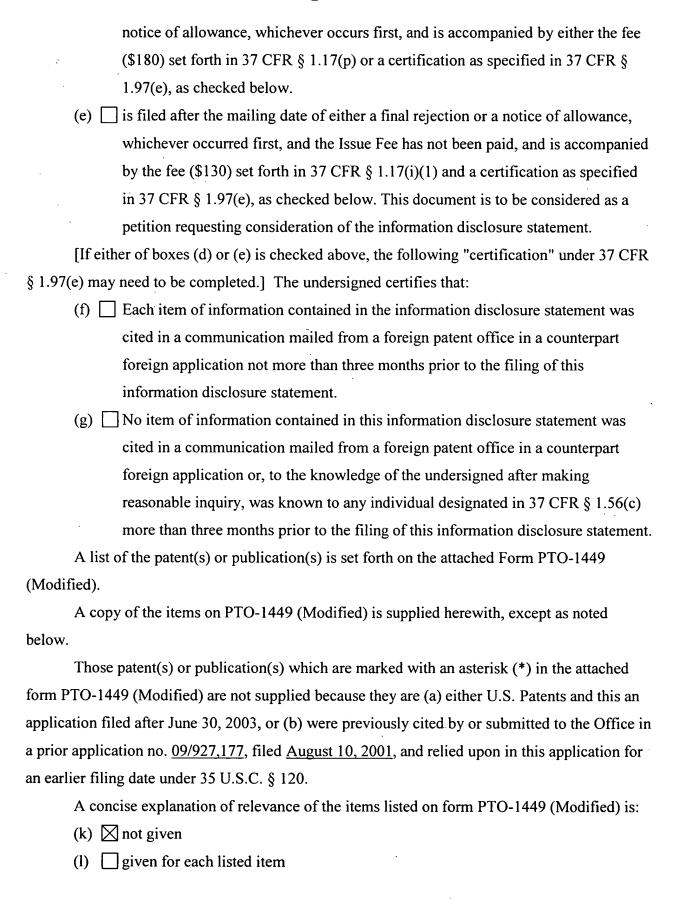
Applicant(s) submit(s) herewith patents, publications or other information [attached hereto and listed on the attached Form PTO-1449 (modified)] of which they are aware, which they believe(s) may be material to the examination of this application and in respect of which there may be a duty to disclose in accordance with 37 CFR § 1.56.

This Information Disclosure Statement:

(a)	⊠ accompanies the new patent application submitted herewith. 37 CFR § 1.97(a).
(b)	is filed within three months after the filing date of the application or within three
	months after the date of entry of the national stage of a PCT application as set
	forth in 37 CFR § 1.491.
(c)	as far as is known to the undersigned, is filed before the mailing date of a first
	Office Action on the merits, or before a first office action after filing a Request
	for Continued Examination under §1.114.
(d)	is filed after the first office action and more than three months after the
	application's filing date or PCT national stage date of entry filing but, as far as is

known to the undersigned, prior to the mailing date of either a final rejection or a

Atty Docket No.: TWI-30510



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(m) given for only non-English language listed item(s) [Required]

(n) is in the form of an English language copy of a Search Report from a foreign patent office, issued in a counterpart application, which refers to the relevant portions of the references [copy attached].

The Examiner is reminded that a "concise explanation of the relevance" of the submitted items "may be nothing more than identification of the particular figure or paragraph of the patent or publication which has some relation to the claimed invention," MPEP § 609.

While the information and references disclosed in this Information Disclosure Statement may be "material" pursuant to 37 CFR § 1.56, it is not intended to constitute an admission that any patent, publication or other information referred to therein is "prior art" for this invention unless specifically designated as such.

In accordance with 37 CFR § 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 CFR § 1.56(a) exists. It is submitted that the Information Disclosure Statement is in compliance with 37 CFR § 1.98 and MPEP § 609 and the Examiner is respectfully requested to consider the listed references.

Respectfully submitted,

STALLMAN & POLLOCK LLP

Dated: February (L. 2004)

Michael A. Stallman Reg. No. 29,444

Attorneys for Applicant(s)

Atty Docket No.: TWI-30510

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional) TWI-30510	Application Number NEW
Applicant(s) Kenneth C. Johnson et al.	
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Examiner	Date Considered					
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if						
not in conformance and not considered. Include copy of this form with next communication to applicant.						

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Filing Date	Group Art Unit	
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Examiner: Initial if citation considered, whether or not citation is in conot in conformance and not considered. Include copy of this form with	, ,